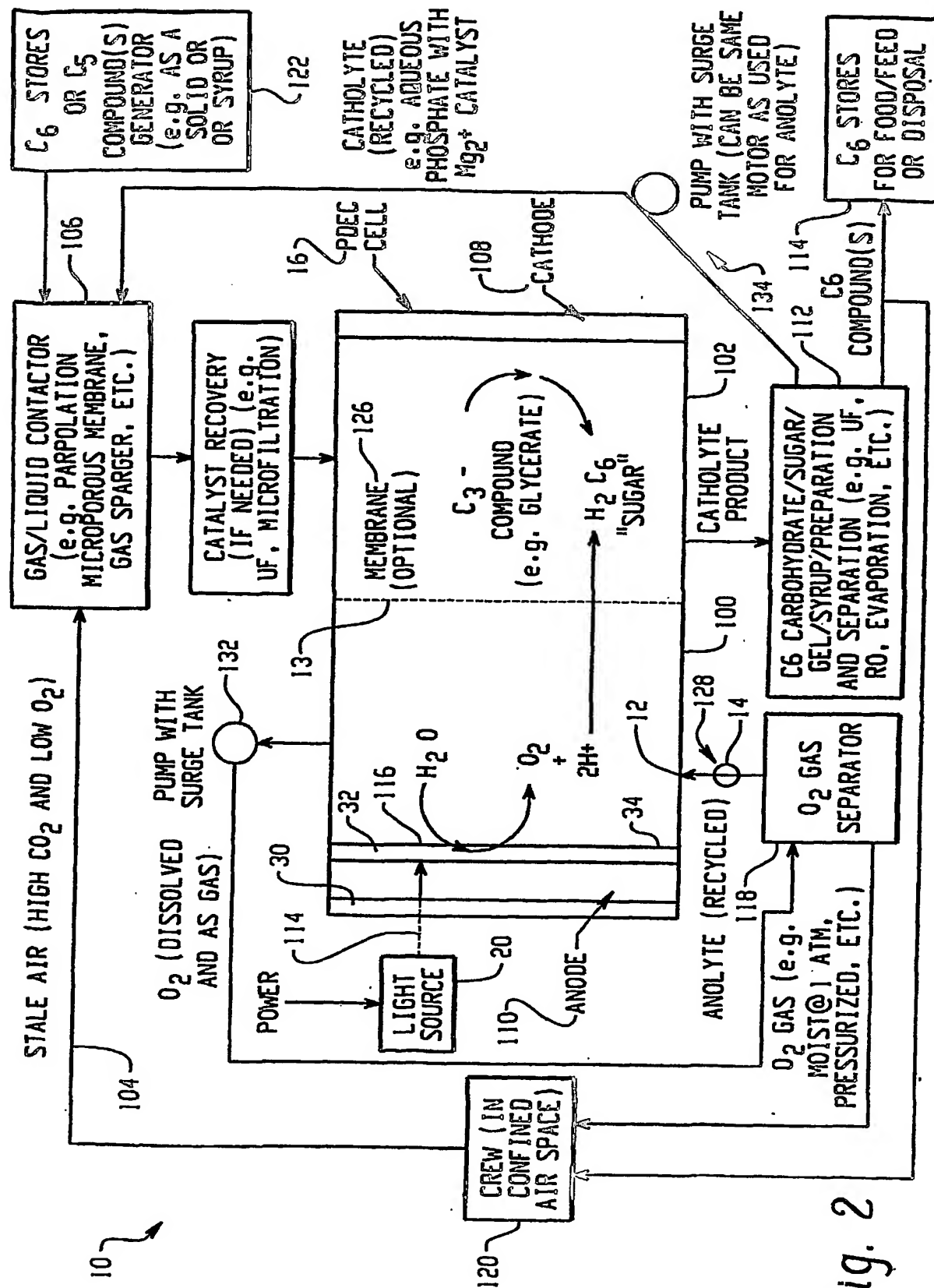


Fig. 1



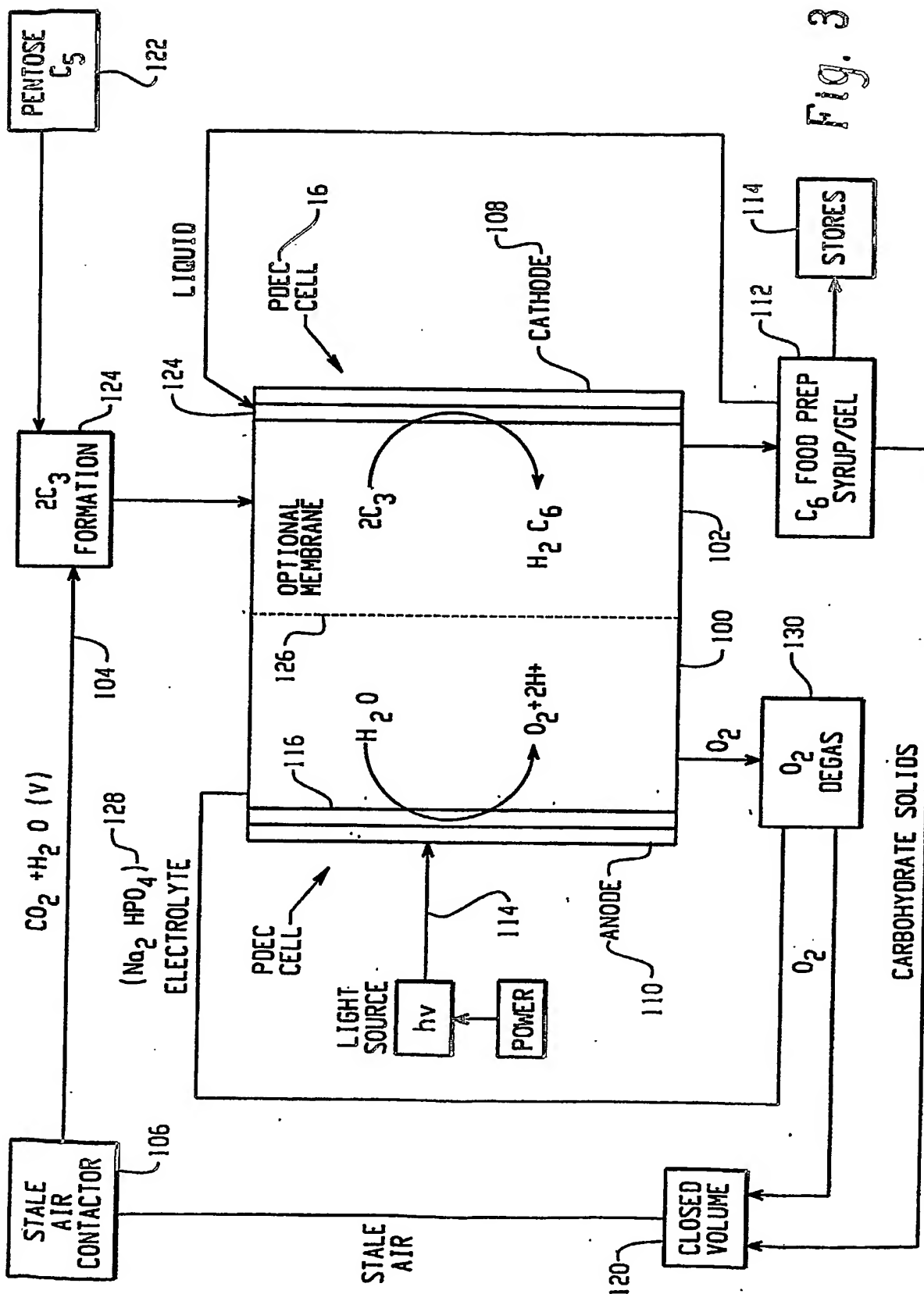


Fig. 3

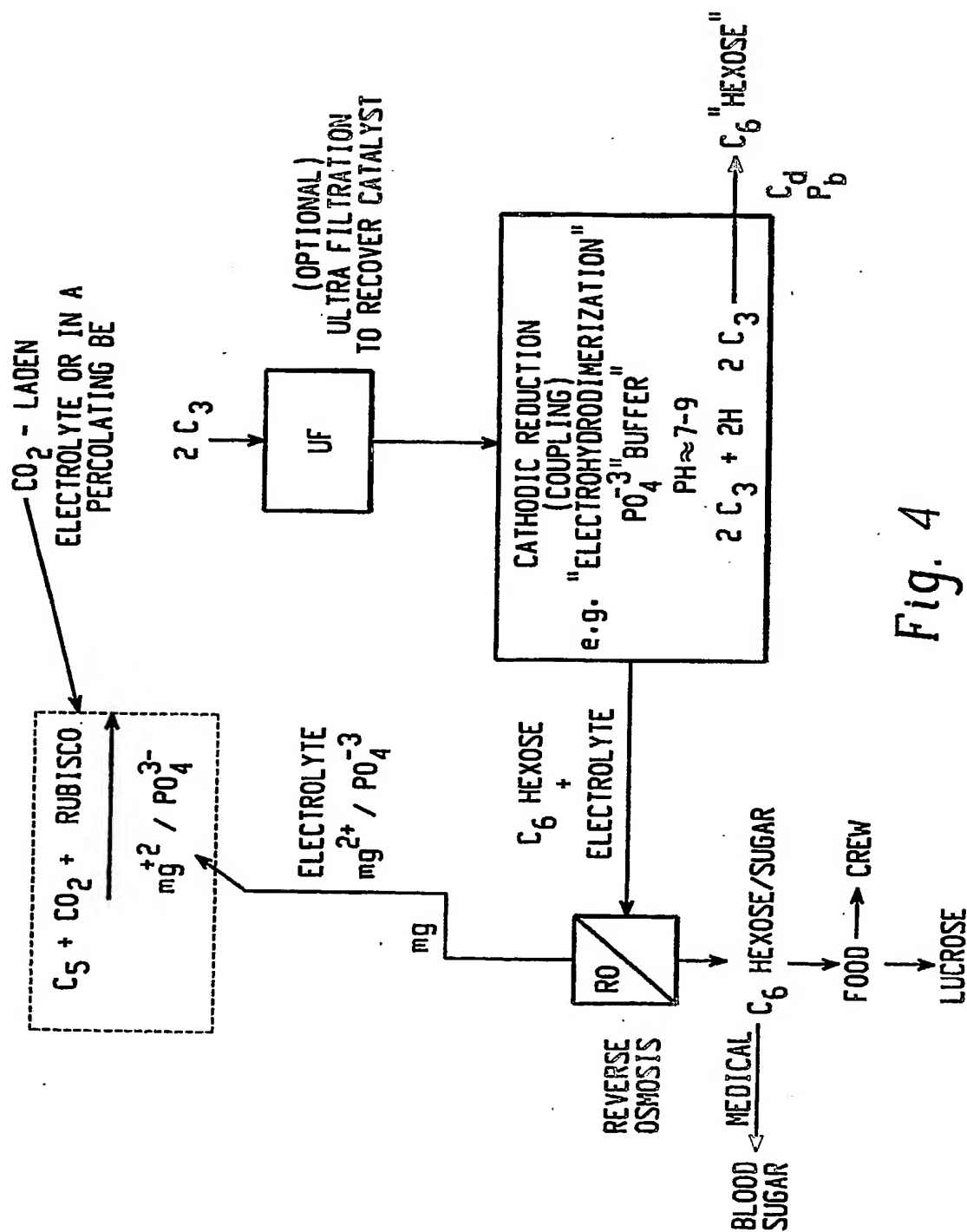


Fig. 4

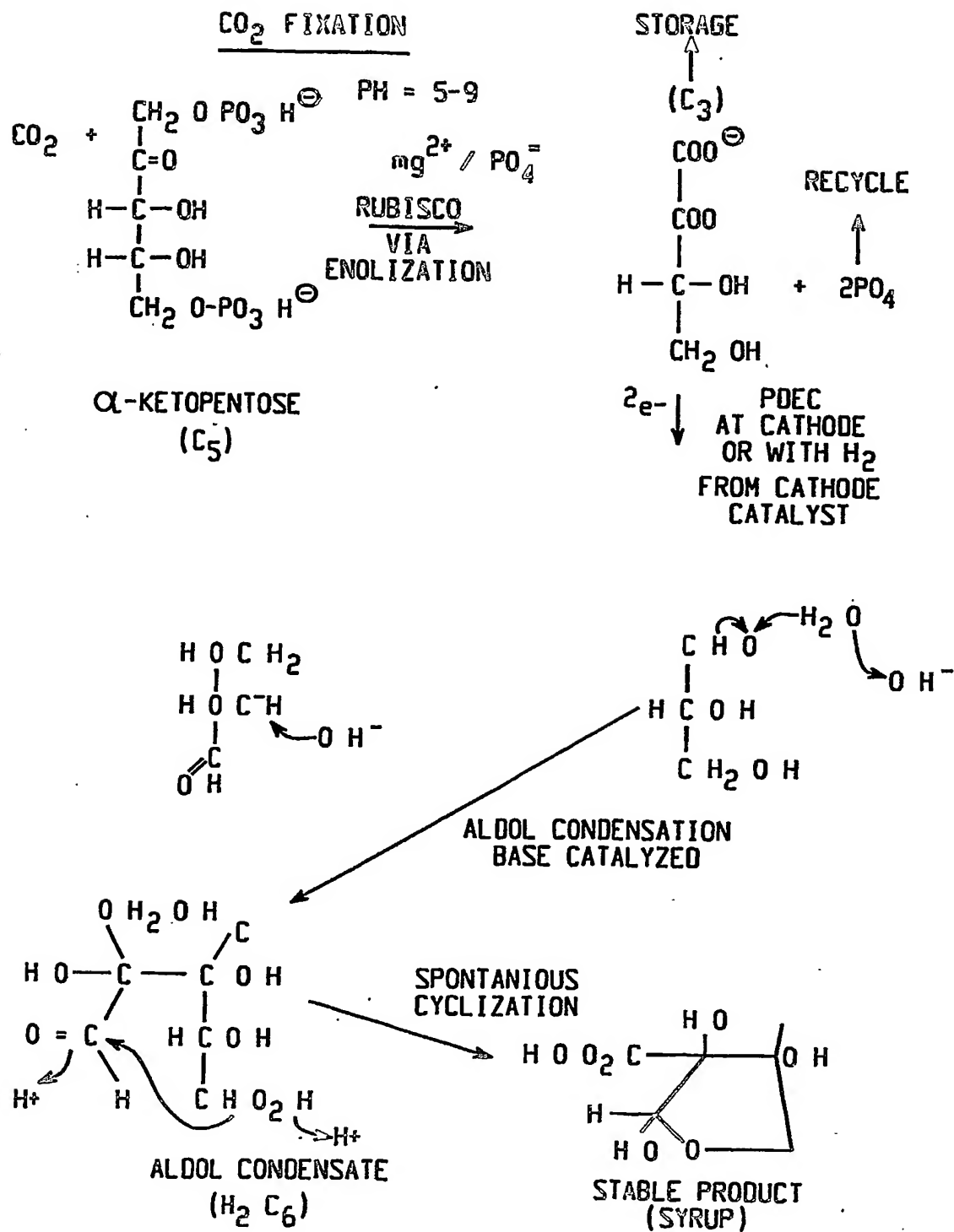


Fig. 5

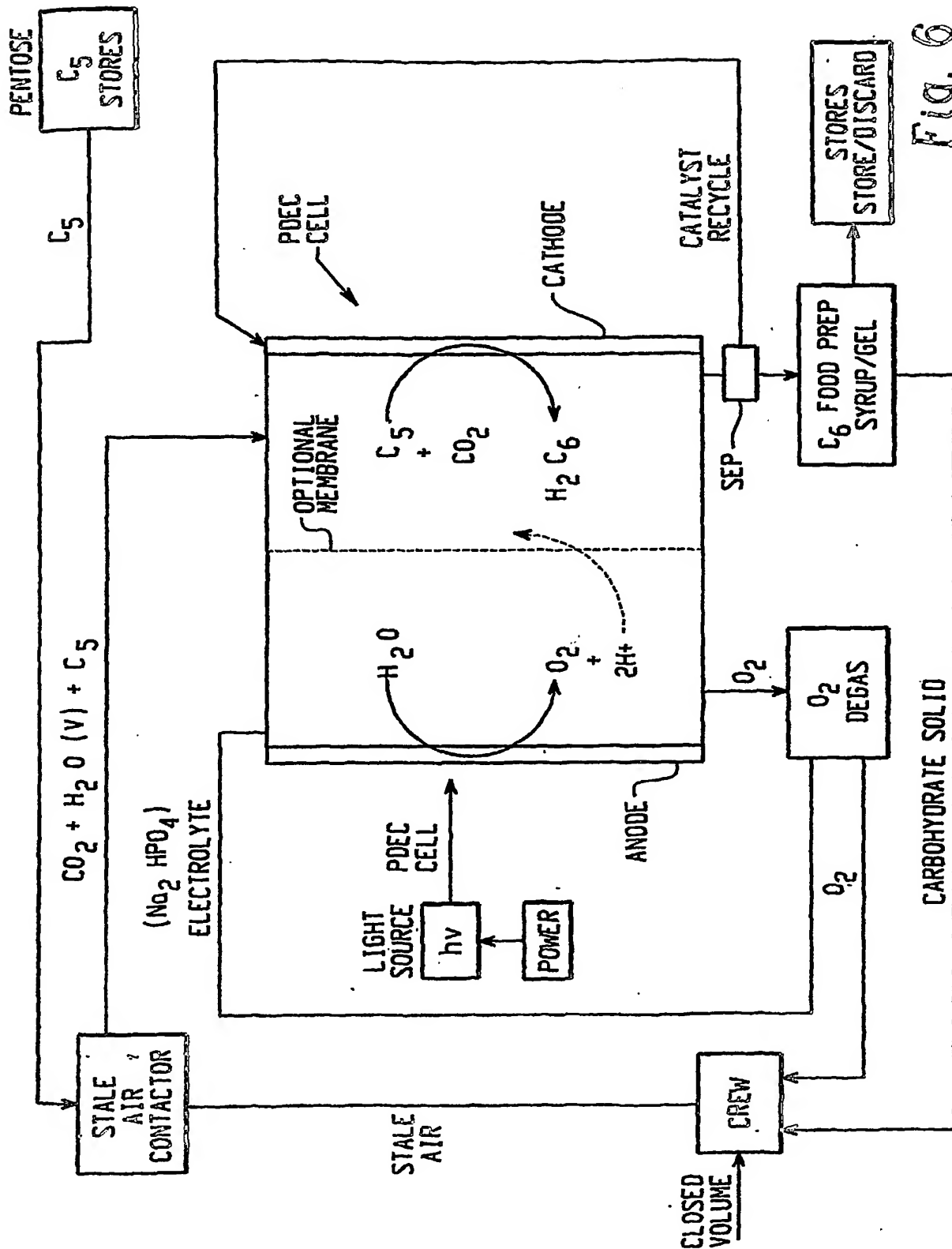


Fig. 6

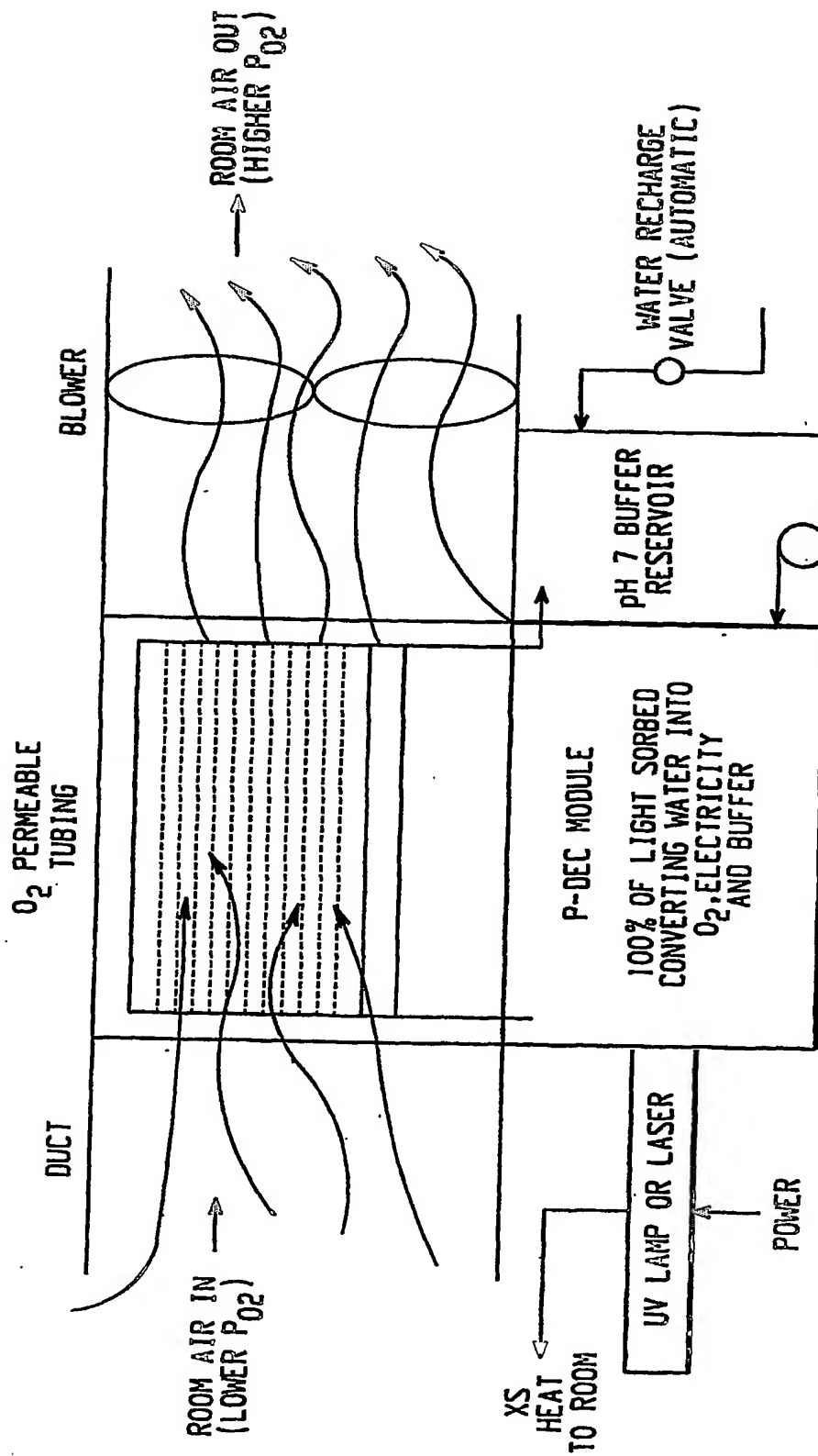


Fig. 7

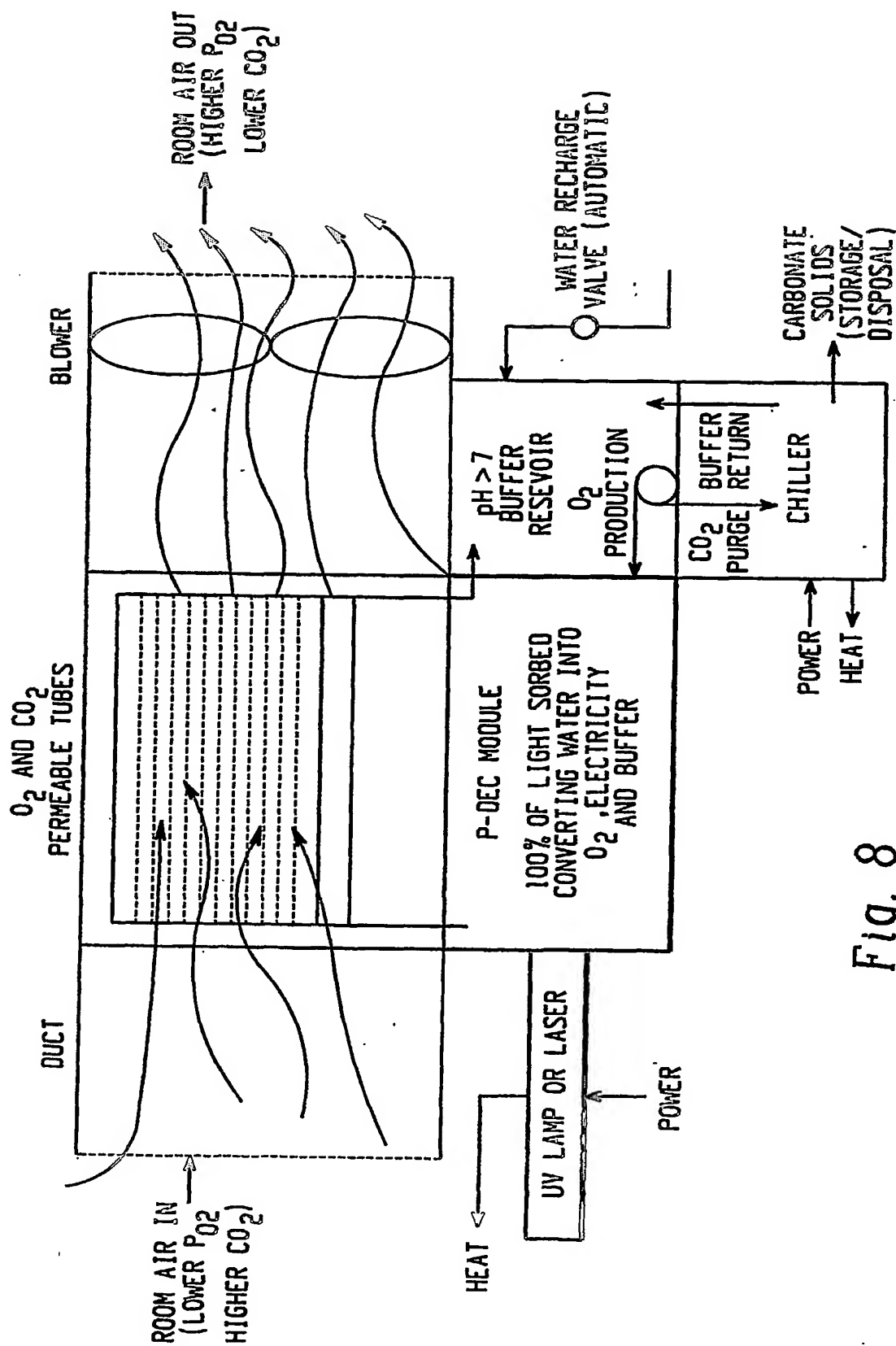


Fig. 8

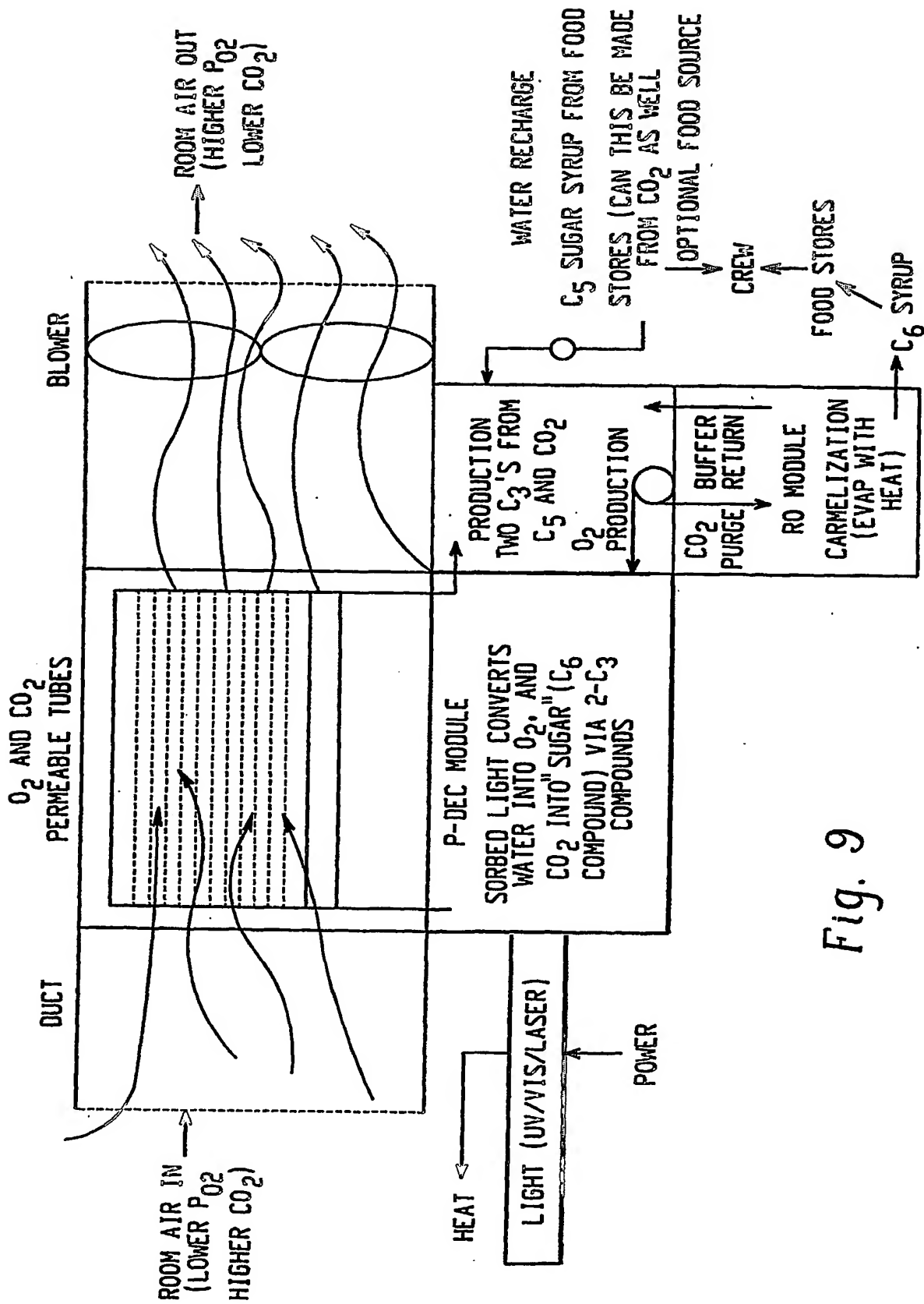


Fig. 9

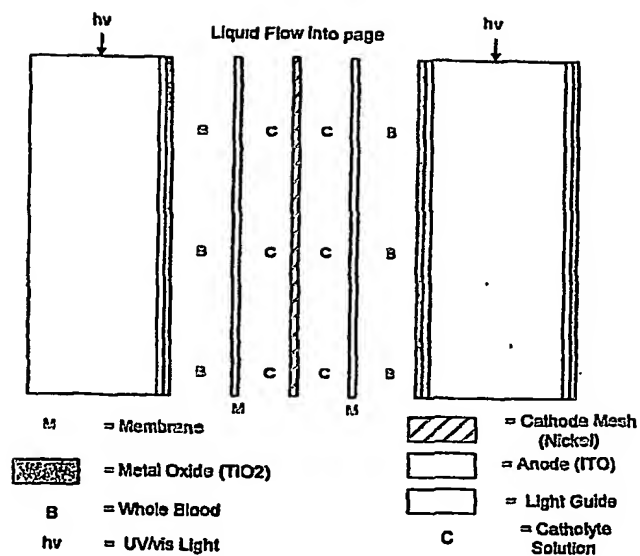


FIGURE 10A

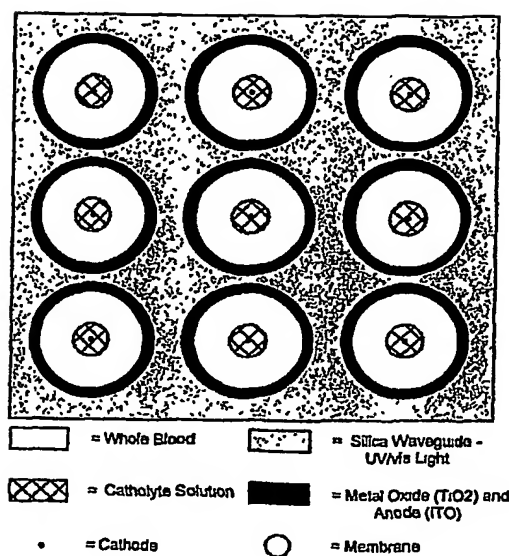


FIGURE 10B

Figures 10A - 10B: Possible geometries for the capillary mimicking structures



FIGURE 11A

FIGURE 11B

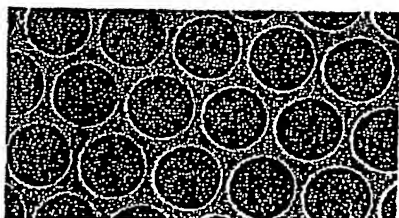


FIGURE 11C

Figures 11A - 11C: Examples of nanopatterned surfaces. Shown are three structures that were generated by photolithography with anisotropic etching in silicon. Left (Figure 11A), light traps. Above right (Figure 11B), ink jet channels. Below right (Figure 11C), EMI mesh filters.

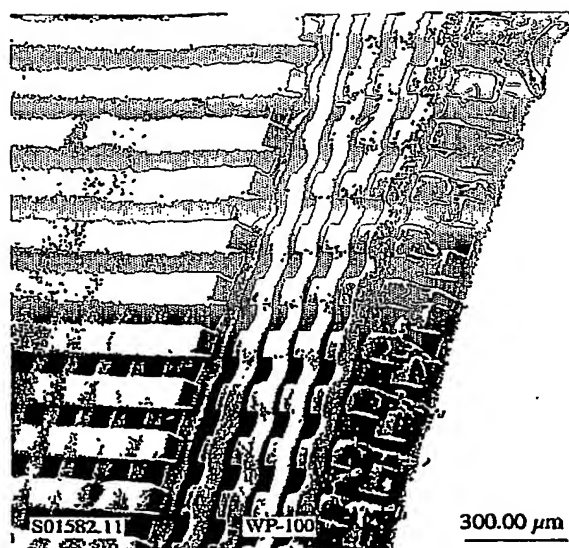


Figure 12: A 3-D mesh structure composed of 100 μ m “sticks” with 100 μ m spacing created by the microfabrication technique developed by Applicant.

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